ABSTRACT

A cleaning device includes: a substrate rotation mechanism that holds ~~a substrate~~ and rotates a~~the~~ substrate around ~~a~~ center axis thereof ~~the substrate as a rotation axis~~; a first single-tube nozzle that discharges ~~a~~ first cleaning liquid toward a top surface of the substrate ~~held by the substrate rotation mechanism~~; and a second single-tube nozzle that discharges ~~a~~ second cleaning liquid toward the top surface of the substrate ~~held by the substrate rotation mechanism separately from the first single-tube nozzle~~. The first single-tube nozzle and the second single-tube nozzle are disposed such that the second single-tube nozzle discharges the second cleaning liquid in a forward direction of a rotation direction of the substrate at a position farther away from the center of the substrate than a landing position of the first cleaning liquid, and a part is generated in which ~~a~~ liquid flow on the top surface of the substrate after landing of the first cleaning liquid and ~~a~~ liquid flow on the top surface of the substrate after landing of the second cleaning liquid are combined.

Figure 2